

## Correlation between material quality and high frequency performance of graphene field-effect transistors

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In this paper, we present an experimental study of correlation between material quality and high frequency performance of graphene field-effect transistors (GFETs). Analysis of the low- and high-field charge carrier transport in a set of GFETs, including those with record high extrinsic transit frequency ( $f_t$ ) and maximum frequency of oscillation ( $f_{max}$ ) [1], indicates presence of spatially distributed imperfections causing both long- and short-range scattering and associated with e.g. charged defects and dislocations [2]. We applied the drain resistance, velocity and saturation velocity models and found the physical and equivalent circuit parameters defining the  $f_t$  and  $f_{max}$ , i.e. the low-field mobility ( $\mu$ ), residual carrier concentration, metal/graphene contact resistivity ( $\rho_{cm}$ ), high-field carrier velocity ( $v$ ) and differential drain conductivity ( $g_{ds}$ ) [3, 4]. Based on the  $\mu$  as a measure of imperfections, we established correlations between all the parameters. As examples, Fig. 1 and Fig. 2 show dependences of the  $v$ ,  $g_{ds}$  and  $f_t$ ,  $f_{max}$  on  $\mu$ . The established correlations allow for understanding dominant limitations of the  $f_t$  and  $f_{max}$ , which clarifies the ways of further development of the GFETs for high frequency applications. For instance, the  $\rho_{cm}$  is below  $30 \Omega\cdot\mu\text{m}$  at  $\mu$  above  $2000 \text{ cm}^2/\text{Vs}$  and has only minor effect. The high  $g_{ds}$ , is currently main limiting factor, which, however, can be counterbalanced by increasing the carrier velocity via operating GFETs at higher fields, in the velocity saturation mode.

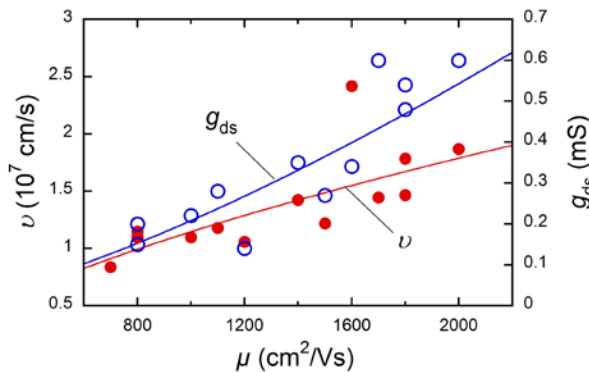


Fig. 1. The high-field velocity of charge carriers,  $v$ , (filled circles) and differential drain conductivity,  $g_{ds}$ , (open circles) vs low-field mobility,  $\mu$ , of GFETs. The lines are power-fitting curves.

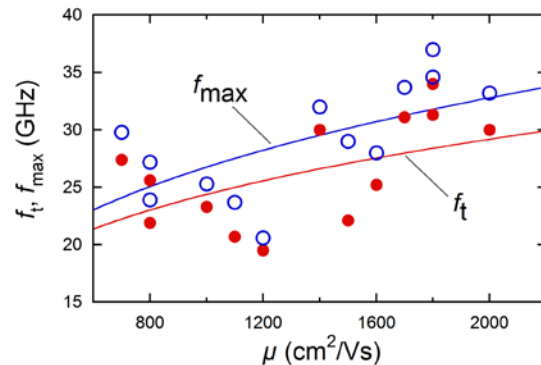


Fig. 2. The measured (extrinsic) transit frequency,  $f_t$ , (filled circles) and maximum frequency of oscillation,  $f_{max}$ , (open circles) vs low-field mobility,  $\mu$ , of GFETs with gate length of  $0.5 \mu\text{m}$ . The lines are power-fitting curves.

### References

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